

CER Laser Ellipsometer

- Unambiguous thickness determination
- Largest measurement range
- It has never been easier to apply ellipsometry to real-world samples

SE 500adv





Laser ellipsometer combined with reflectometer

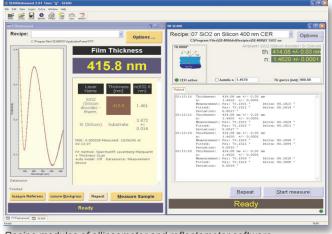
Product description

The **SE 500adv** combines ellipsometry and reflectometry to eliminate the ambiguity of measuring layer thickness of transparent films. It extends the measureable thickness to $25\,\mu m$. Therefore, the **SE 500adv** extends the capability of standard laser ellipsometer **SE 400adv** especially for analyzing thicker films of dielectrics, organic materials, photoresists, silicon, and polysilicon.

The **SE 500adv** can be operated as **laser ellipsometer**, as **film thickness probe**, and as **CER ellipsometer**. Operated as laser ellipsometer, single and multiple angle measurements can be performed. When operated as film thickness probe, the thickness of a transparent or weakly absorbing film is measured under normal incidence. So, the **SE 500adv** offers maximum flexibility never reached by standard laser ellipsometers.

The CER ellipsometer **SE 500adv** comprises the ellipsometer optics, goniometer, combined reflection measurement head and auto-collimating telescope, sample platform, HeNe laser source, laser light detection unit, and photometer.

The options of the **SE 500adv** support applications in microelectronics, mircosystems technology, display technology, photovoltaics, chemistry, and others.



Recipe modules of ellipsometer and reflectometer software

SE 500adv CER Laser Ellipsometer

- Combines ellipsometry and reflectometry
- Eliminates the ambiguity in layer thickness determination for transparent films
- Extends thickness measurement to 25 µm
- It has never been easier to apply ellipsometry to real-world samples

Specifications

Precision of Ψ , Δ at 90° δ (Ψ) = 0.002° (transmission) position: δ (Δ) = 0.002°

Long term stability: $\delta (\Psi) = \pm 0.01^{\circ}$

 $\delta (\Delta) = \pm 0.1^{\circ}$

Precision

of film thickness: 0.1 Å for 100 nm SiO₂ on Si

Precision

of refractive index: 5×10^{-4} for 100 nm SiO_2 on Si

Laser wavelength: 632.8 nm

Diameter of laser spot: 1 mm

Spectral range of

reflectometer: 450 nm to 920 nm

Spot size reflectometer: 80 µm

Sample alignment: Auto collimating telescope (ACT)

for manual sample tilt and height

adjustment

Options

- Microspots (25 µm)
- Mapping stages (50 mm to 300 mm)
- · Liquid cells
- Video camera
- Autofocus
- Video camera
- · Computer controlled goniometer
- Simulation software
- · Certified reference wafers

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